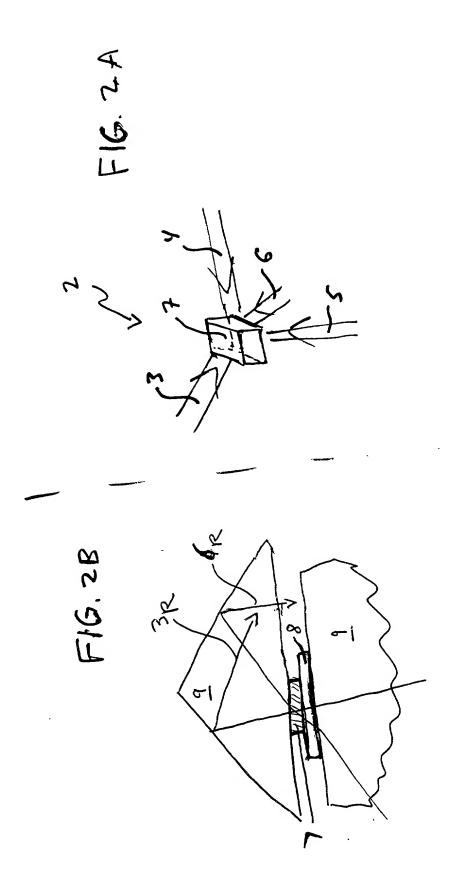
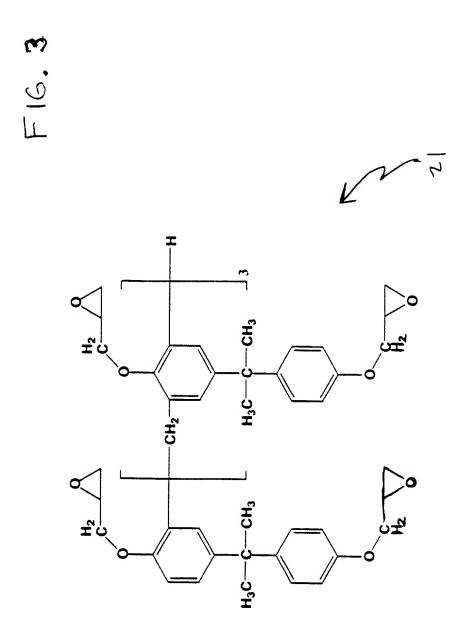
P \alpha
Provide photo-sensitive medium
L12
France W
Expose the medium to an intensity pattern under conditions that inhibit refractive index changes
-14
Heat the exposed medium to favorize refractive index chamins
refractive index changing reactions
reactions
-16
Wash +1
wash the cured medium to remove
either reacted or unreacted portions of the medium
48
Pru the
conditions to the medium under
Dry the washed medium under conditions that limit internal stresses
C ₂₀
\mathcal{N}
F16.1





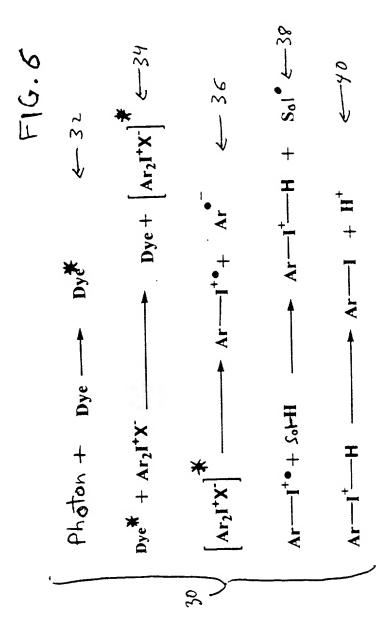
F16.4A

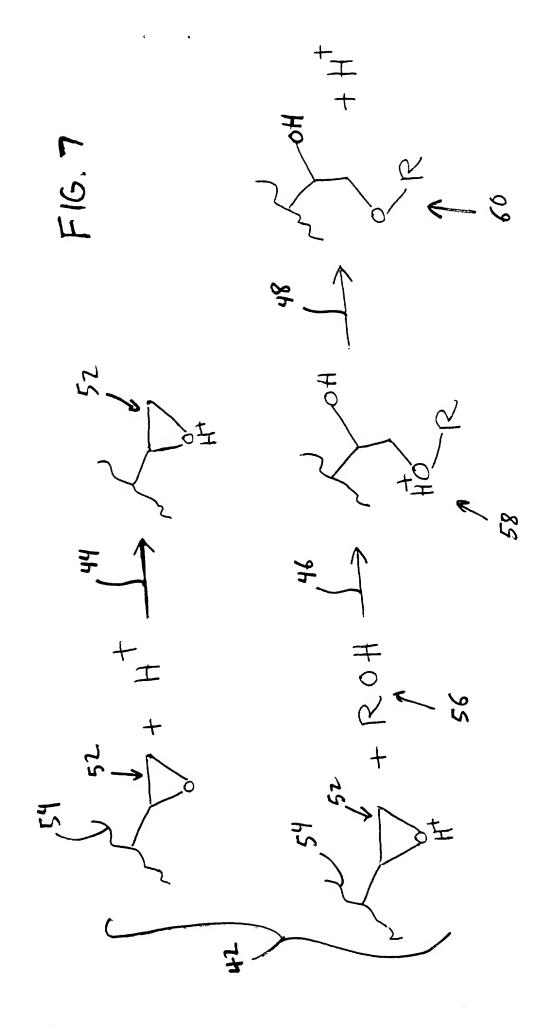
F16.48

F16.4C

F16.5A

F16.5B





Provide Photo-sensitive medium
C12
Expose the medium to an intensity-pattern
under conditions that inhibit refractive index changes
14
Segnentially expose a selected set
Segnentially expose a selected set of points and/or lines with a focal
region of a converging light beam
72
Heat the exposed medium to
favorize polymerization of oligones therein
C16
Wash the cured medium to remove
unpolymerized oligomers
C18
Dry the washed medium under conditions that limit internal stresses
2
70 F16.8

Form a 3D polymer crystalline temy	olate
. L8Z	
Fill holes in the template with a hirefractive index filler material	righ
684	
Burn or etch away the polymer stalling template from the block	cry-
~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~~	
. 80 E10	9

